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E0819

AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1. (Original): A system for dispensing resist, comprising:
 - a reservoir;
 - a nozzle in fluid communication with the reservoir; and
 - a return line in fluid communication with the reservoir;wherein the nozzle is moveable between first and second positions;
in the first position, the nozzle is positioned to dispense liquid from the reservoir onto a substrate; and
in the second position the nozzle is positioned to dispense liquid from the reservoir into the return line.
2. (Original): The system of claim 1, the return line has a coupling with a shape complementary to that of the nozzle and the nozzle is fit into the coupling when the nozzle is in the second position.
3. (Original): The system of claim 2, the reservoir is below the return line coupling.
4. (Original): The system of claim 1, the reservoir has a port out which gas released from liquid in the reservoir is exhausted.
5. (Original): The system of claim 1, the nozzle has a tip approximately in the shape of a truncated cone and a circumference of the conc at its base is at least about 10 times a circumference of the conc where it is truncated.

10/000,208

E0819

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6. (Original): The system of claim 1 wherein the nozzle has a tip approximately in the shape of a truncated cone, the tip has an orifice on the truncated end, and a circumference of the cone at its base is at least about 10 times a circumference of the orifice.
7. (Original): The system of claim 1, wherein the return line has a trap.
8. (Original): The system of claim 1, the return line exhausts into a holding tank that is separate from the reservoir.
9. (Original): The system of claim 1, wherein the reservoir contains a resist solution.
10. (Original): The system of claim 1, wherein the return line is capped when the nozzle is in the first position.
11. (Original): The system of claim 1, further comprising a pump that pumps fluid from the reservoir to the nozzle and a fluid from the return line flows into the reservoir by the action of gravity.
12. (Original): The system of claim 11, a residence time of resist within the return line is less than about 10 minutes.
13. (Currently Amended): A system for dispensing resist solution, comprising:
a reservoir for containing resist solution;
means for dispensing resist solution from the reservoir onto a substrate; and
means for capturing resist solution dispensed by the dispensing means and returning dummy dispensed resist the dispensed fluid to the reservoir.

10/000,208

E0819

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14. (Withdrawn): A method of dispensing resist, comprising:
- drawing resist from a reservoir;
 - dispensing resist through a dispense head onto a substrate;
 - dummy dispensing resist to mitigate residues on the dispense head;
 - capturing dummy dispensed resist; and
 - returning dummy dispensed resist to the reservoir.
15. (Withdrawn): The method of claim 14, the dummy dispensed resist is captured by coupling the dispense head with a return line.
16. (Withdrawn): The method of claim 15, an atmosphere through which dummy dispensed resist flows is substantially saturated with vapor from the resist solution.
17. (Withdrawn): The method of claim 14, the dummy dispensed resist is filtered shortly after it is captured.
18. (Withdrawn): The method of claim 14, the dummy dispensed resist is immediately returned to the reservoir.
19. (Withdrawn): The method of claim 14, further comprising adding solvent to the dummy dispensed resist before returning the dummy dispensed resist to the reservoir.
20. (Withdrawn): The method of claim 14, further comprising testing the dummy dispensed resist before returning it to the reservoir.